

Recent activities in TITAN Lab

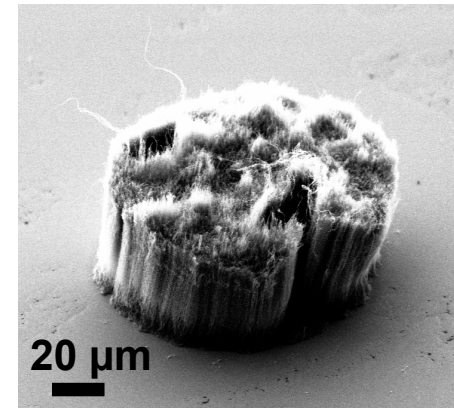
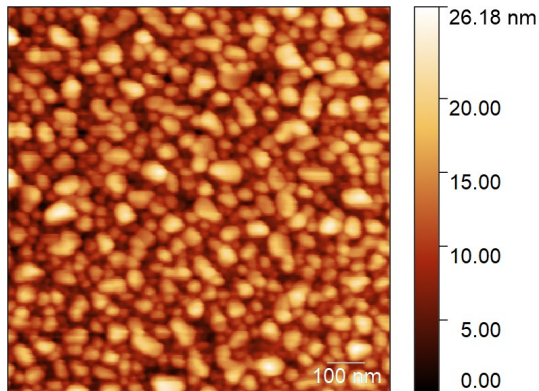
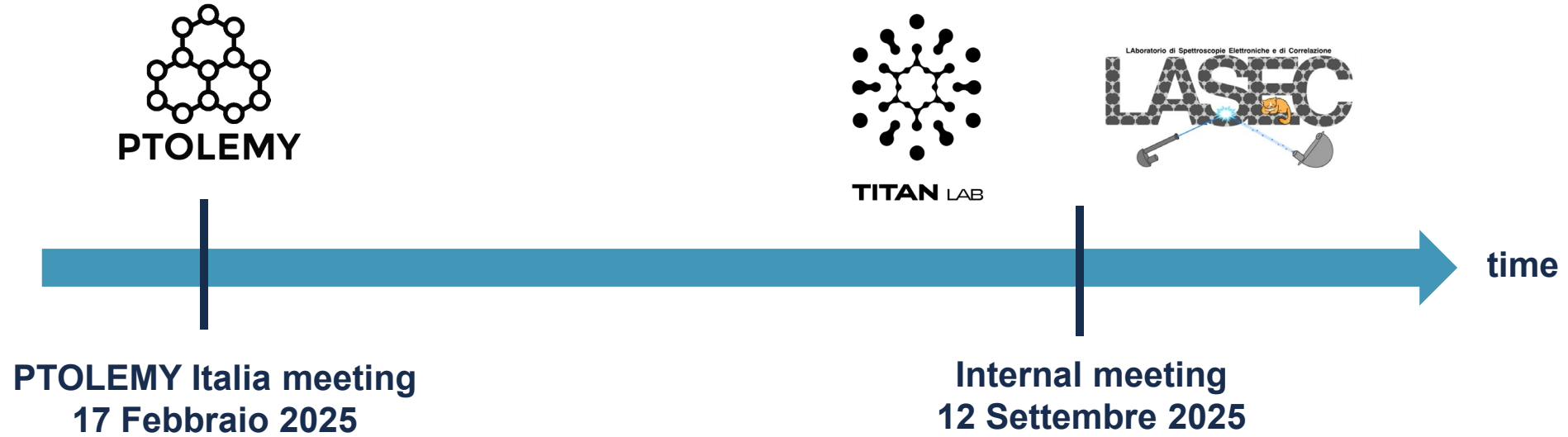
Towards autonomous synthesis of VACNTs

Luca Cecchini

PTOLEMY/ANDROMeDa Meeting

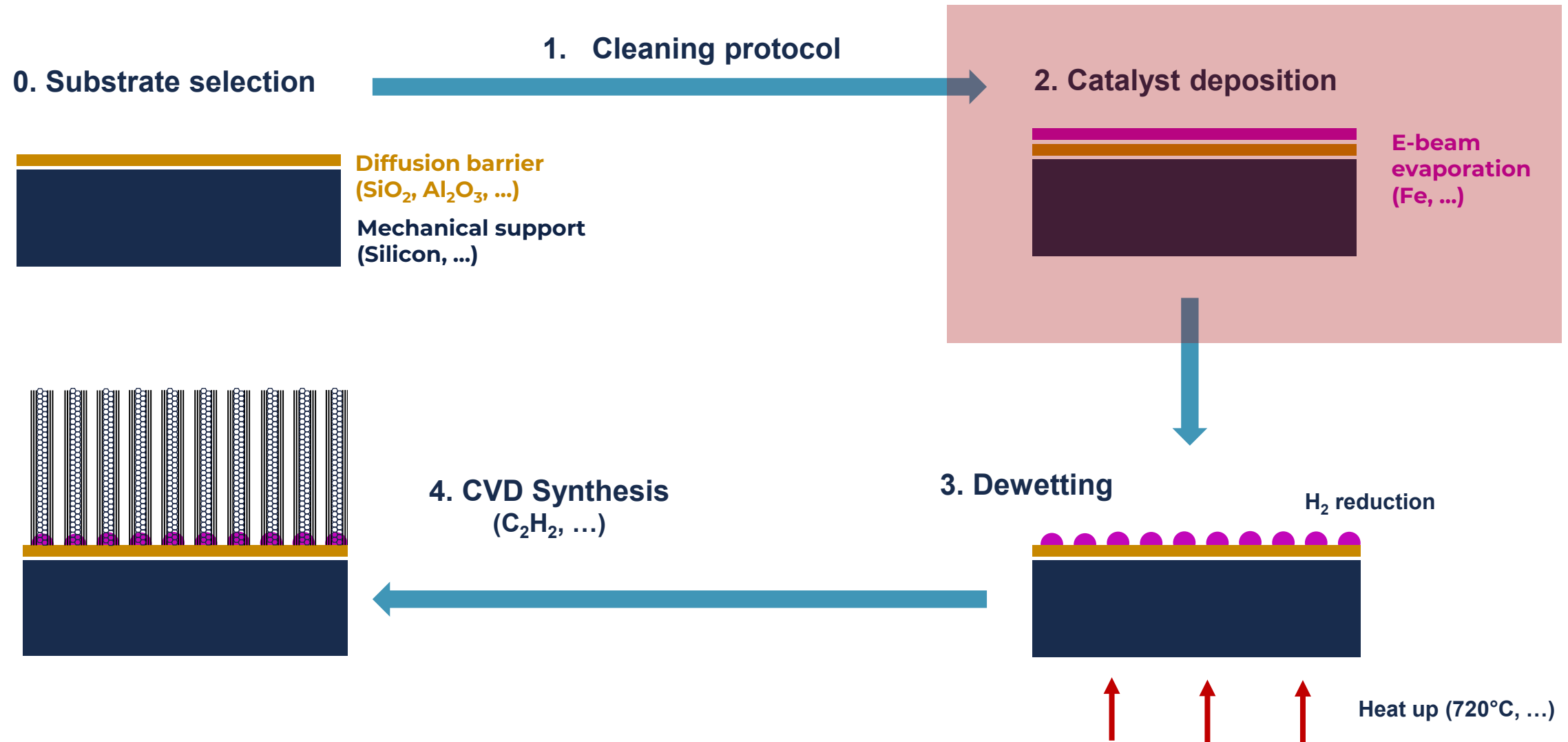
September 12^o, 2025

“Historical” recap



- Non-lithographic synthesis of VACNTs
- E-beam evaporator
- Iron nanostructuring: dewetting analysis
- TCVD growth: the very first problem
- Substrate cleaning and surface activation
- Increase catalyst reactivity: Plasma dewetting and/or hydrogen flux during growth
- Future activities

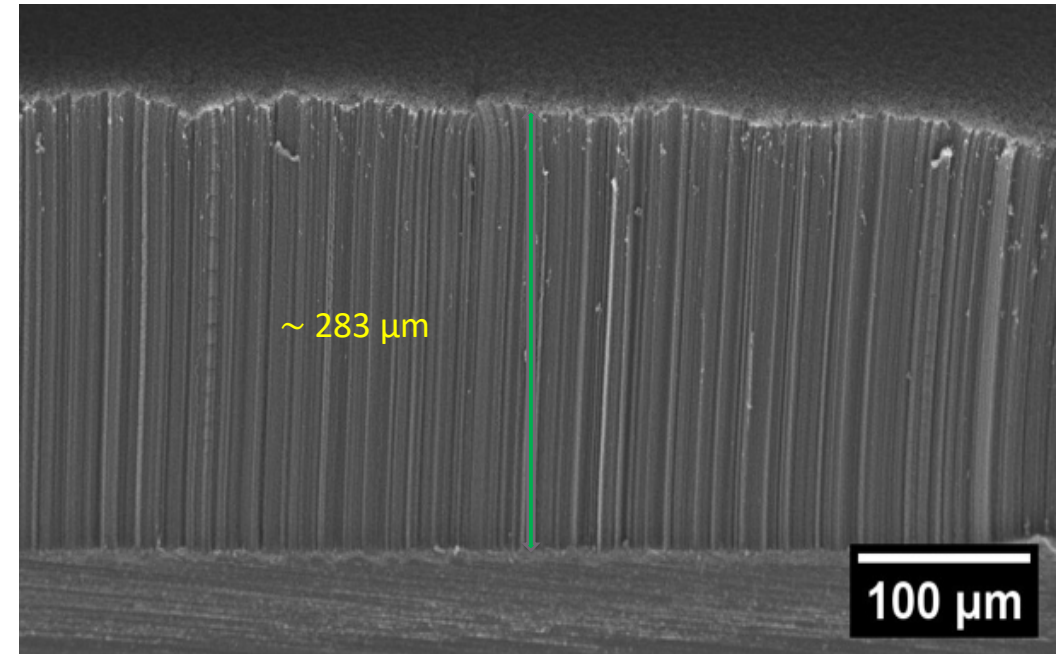
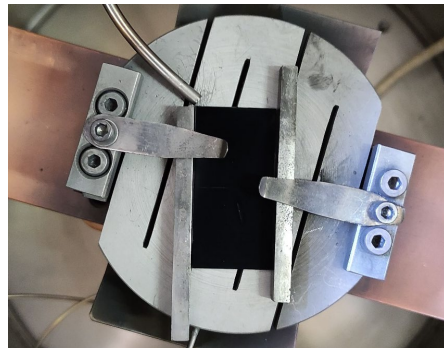
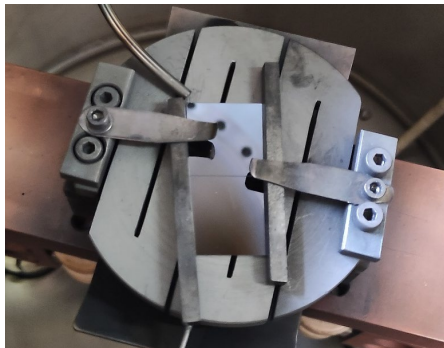
Non-lithographic synthesis of VACNTs

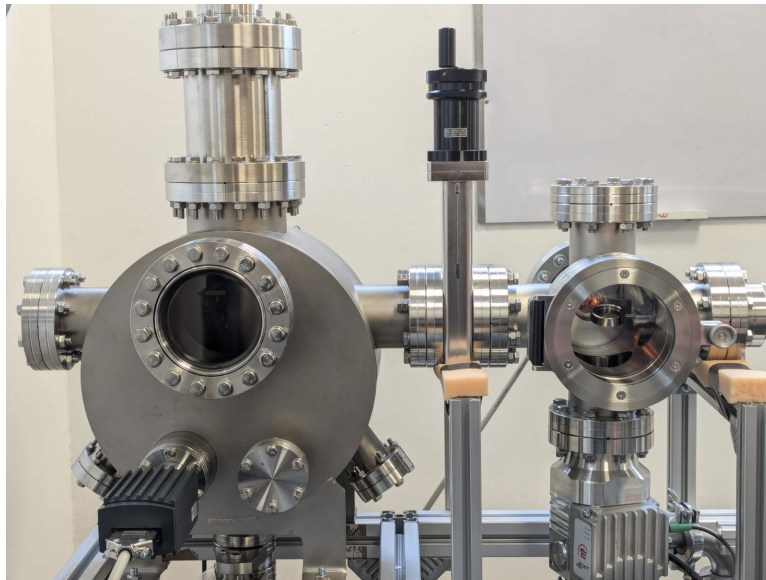


Electron beam evaporator

Fe deposition protocol: PoliFab@PoliMi

- **Environment:** Cleanroom ISO6
- **Substrate:** Si/SiO₂
- **Cleaning:** RCA1
- **Evaporation:** 3nm Fe
- **Transport:** Kitchen vacuum



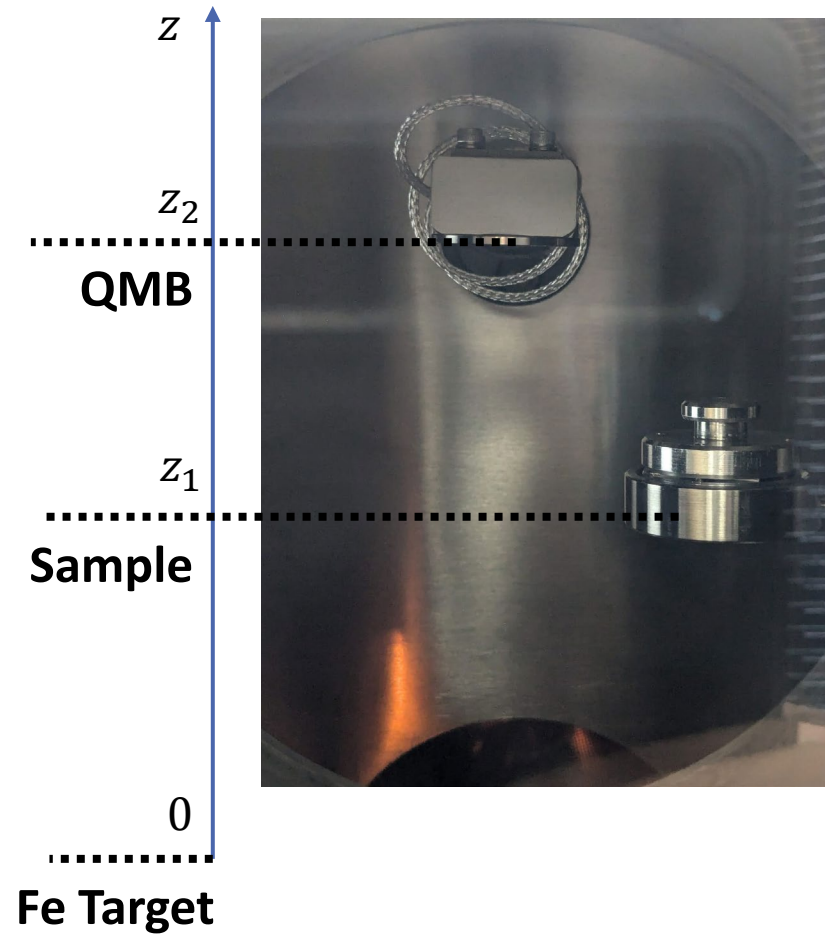
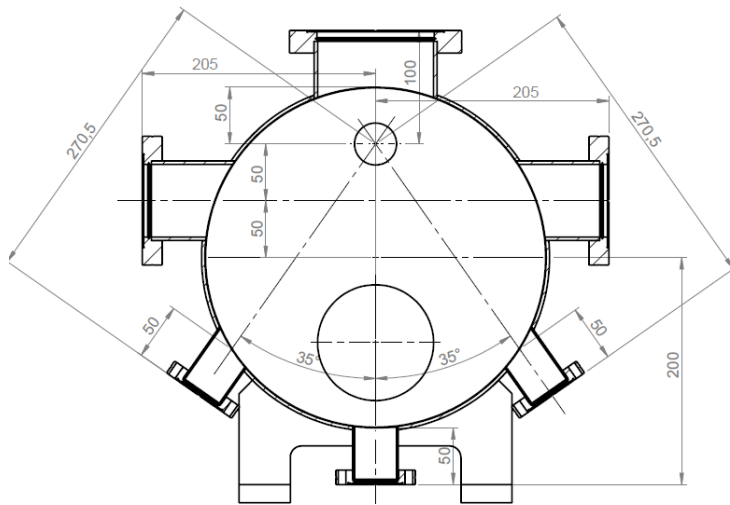


Specifications

- **Sample dimension :** up to $2 \times 2 \text{ cm}^2$
- **Deposition rate :** Quartz Microbalance
- **Bake-out:** Filament and target 250°C for 3h
Chamber 110°C for 48h
- **Operation pressure:** $1 \times 10^{-9} \text{ mbar}$
- **Single source:** Fe 99.95%
- **Filament:** Thoriated (1%) tungsten
Full autonomous technical support
- **Angle aperture:** 6.9°

Deposition Rate

$$\phi(z_1) = \phi(z_2) \left(\frac{z_2}{z_1} \right)^2$$

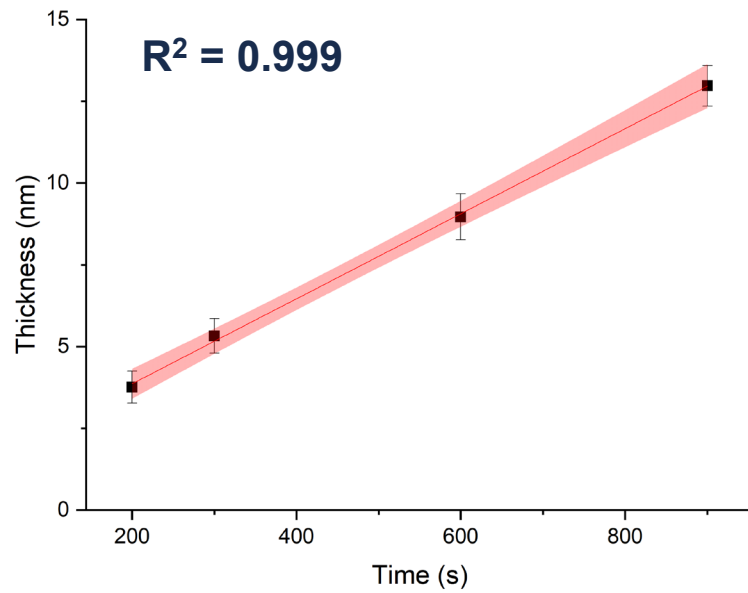


Geometrical estimation

$$\phi(z_1) = \phi(z_2) \left(\frac{z_2}{z_1} \right)^2 = 0.05 \pm 0.01 \frac{\text{\AA}}{\text{s}} \left(\frac{132}{82} \right)^2 = 0.13 \pm 0.03 \frac{\text{\AA}}{\text{s}}$$

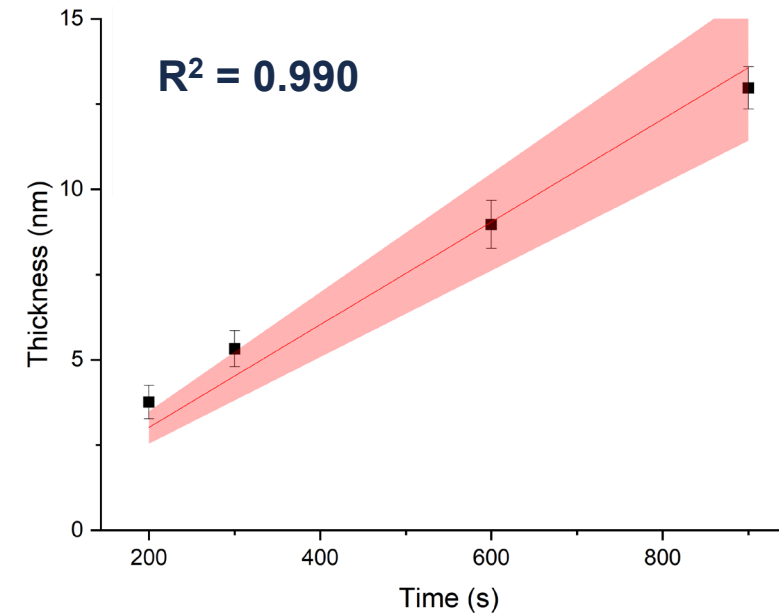
Linear fit with free intercept

$$\phi(z_1) = 0.130 \pm 0.002 \frac{\text{\AA}}{\text{s}}$$



Linear fit with fixed zero intercept

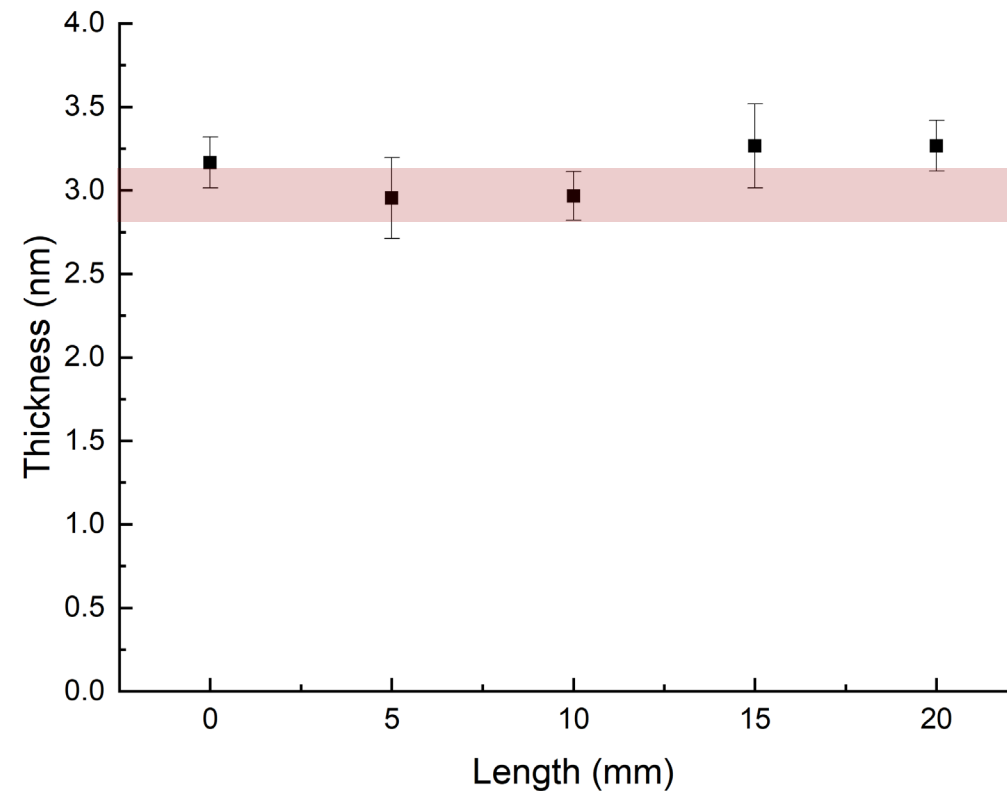
$$\phi(z_1) = 0.150 \pm 0.007 \frac{\text{\AA}}{\text{s}}$$



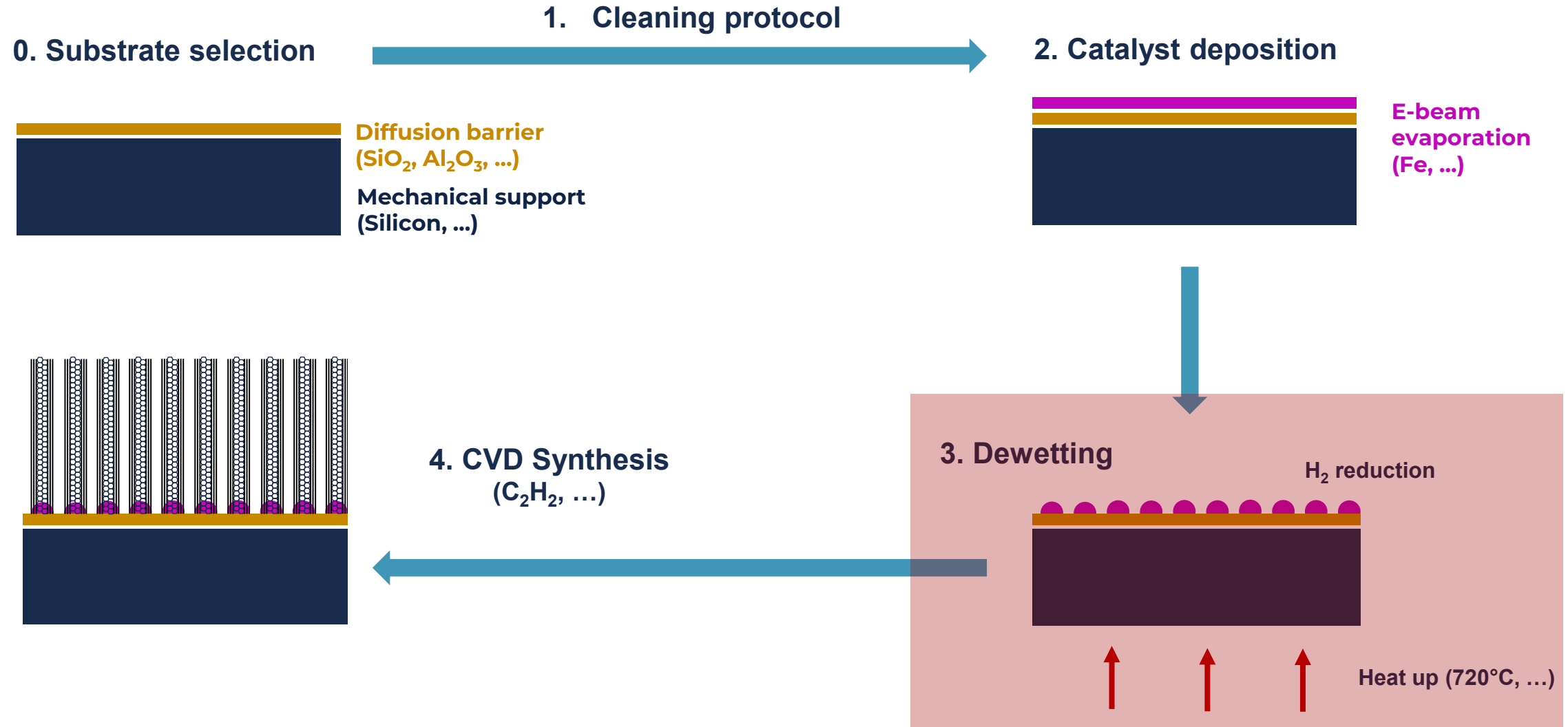
Uniformity Test

There is no statistically significant difference.
Uniform evaporation.

Increase sensitivity using **ellipsometry**, instead of AFM.

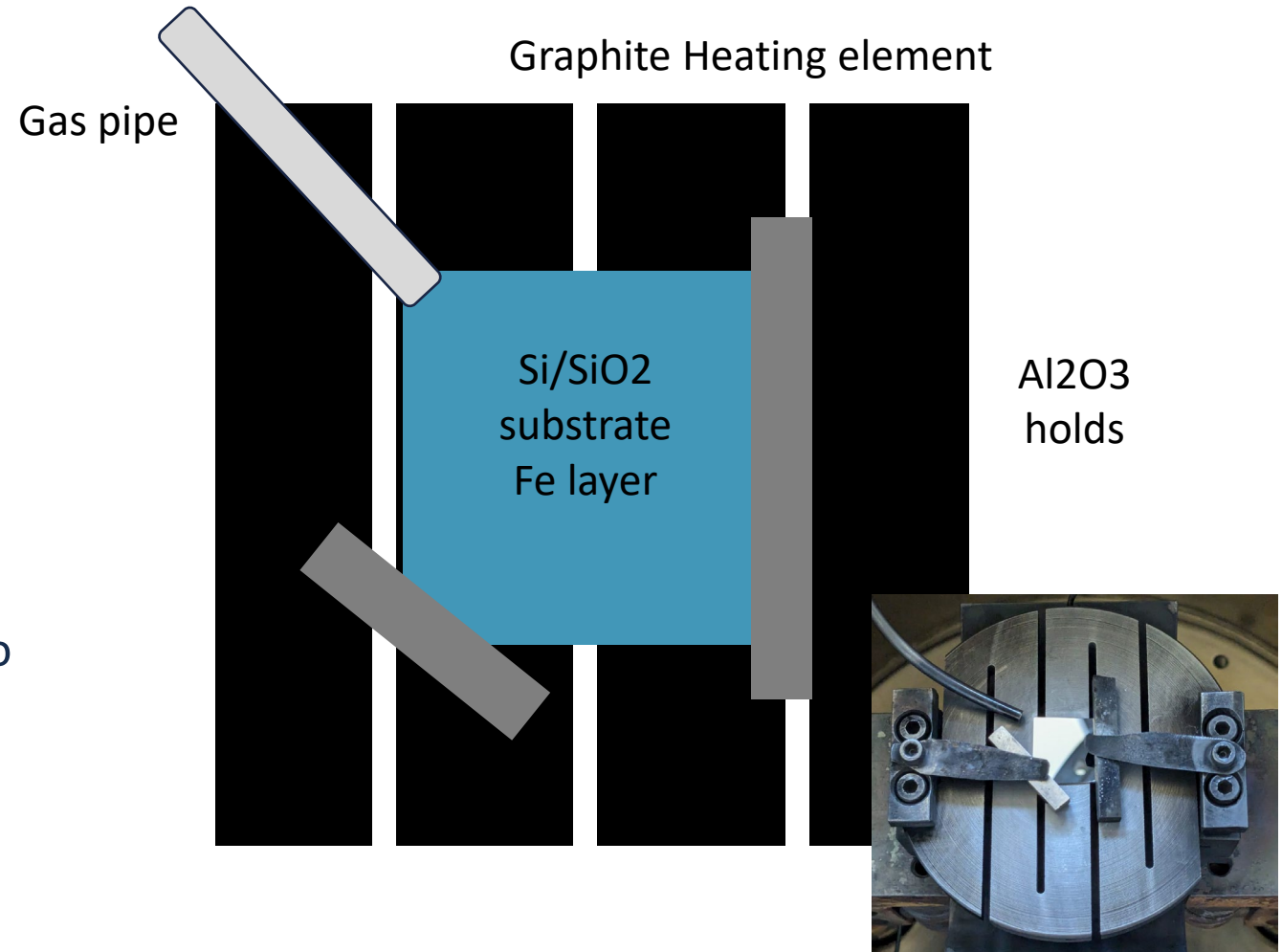


Non-lithographic synthesis of VACNTs



Iron Dewetting

- Emulate the CleanRoom protocol under chemical hood: RCA1
- Use the standard dewetting protocol: 720°C for 4mins
flush H_2 with a linear ramp from 10^{-1} mbar to 8×10^{-1} mbar
- Fix sample dimension and holder position to guarantee same temperature gradient.



Cleaning protocol: RCA1

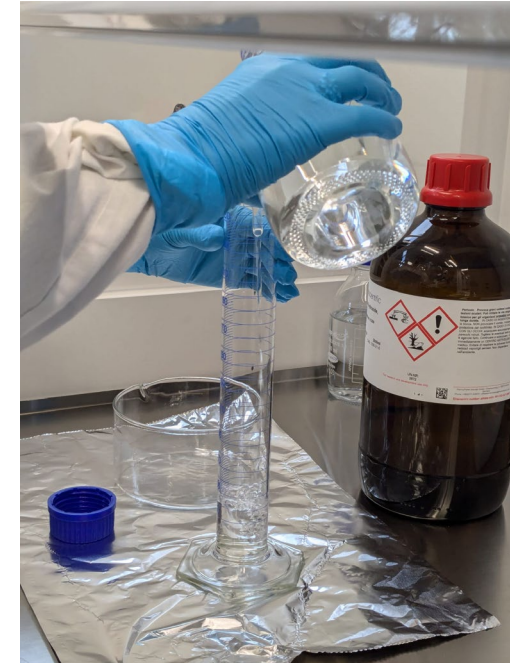
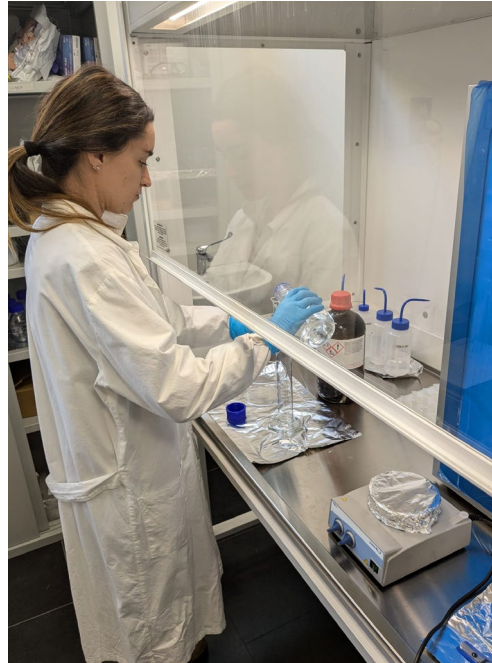
- 150ml DIW
- 30ml Ammonium Hydroxide (30%)

Heat the solution @ 70°C with heating plate (Value 2-3 for 5mins).
Remove the solution from heating plate.

Add:

- 30ml Oxygen Peroxide (28%)

Put the silicon wafer faced-up in the solution for 15mins.
Wash substrate with MilliQ.
Flush with nitrogen.



Comparison between cleaning protocols

From thermodynamic point of view, the **minimum droplet radius** R_{min} is

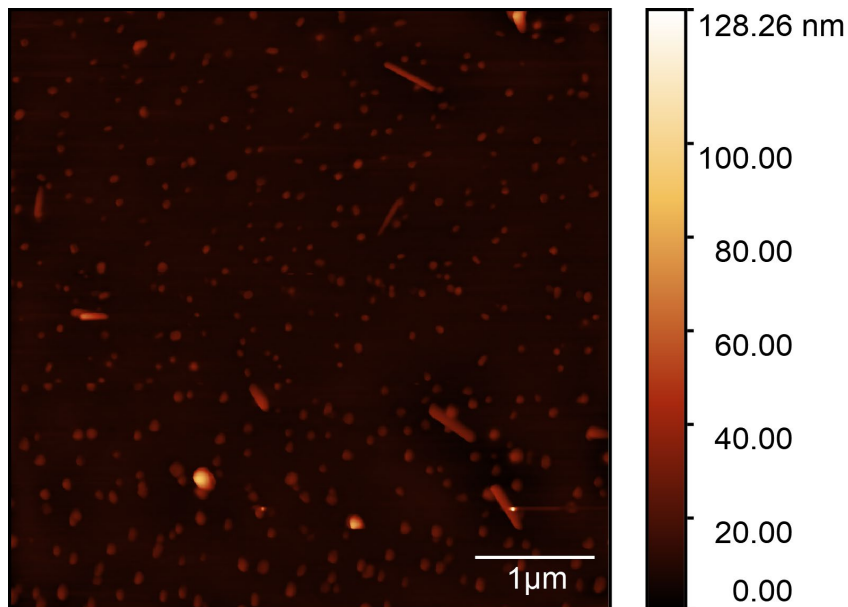
$$R_{min} = \frac{2V_l}{R \cdot T \cdot \ln(s)} \cdot \sigma_{lv}$$

V_l → molar volume of the droplet

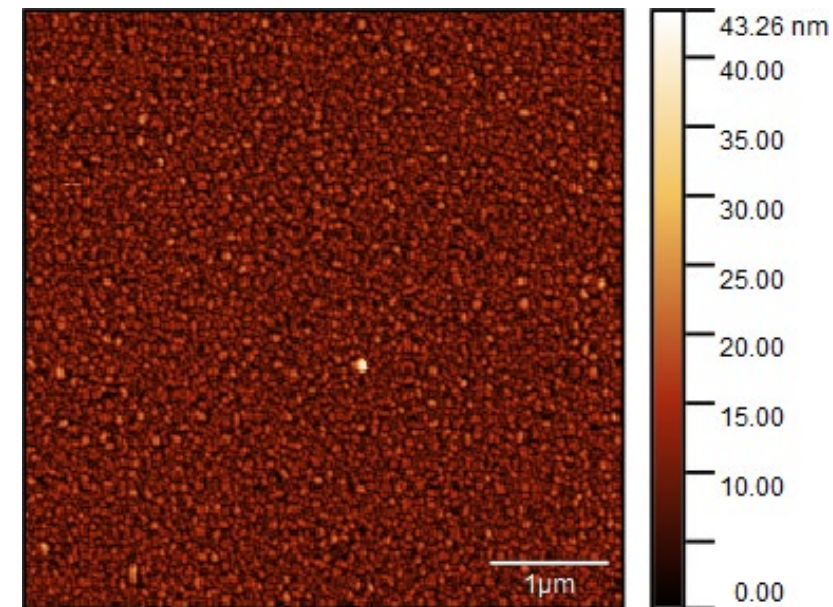
s → degree of supersaturation

σ_{lv} → surface tension at the liquid-vapor interface

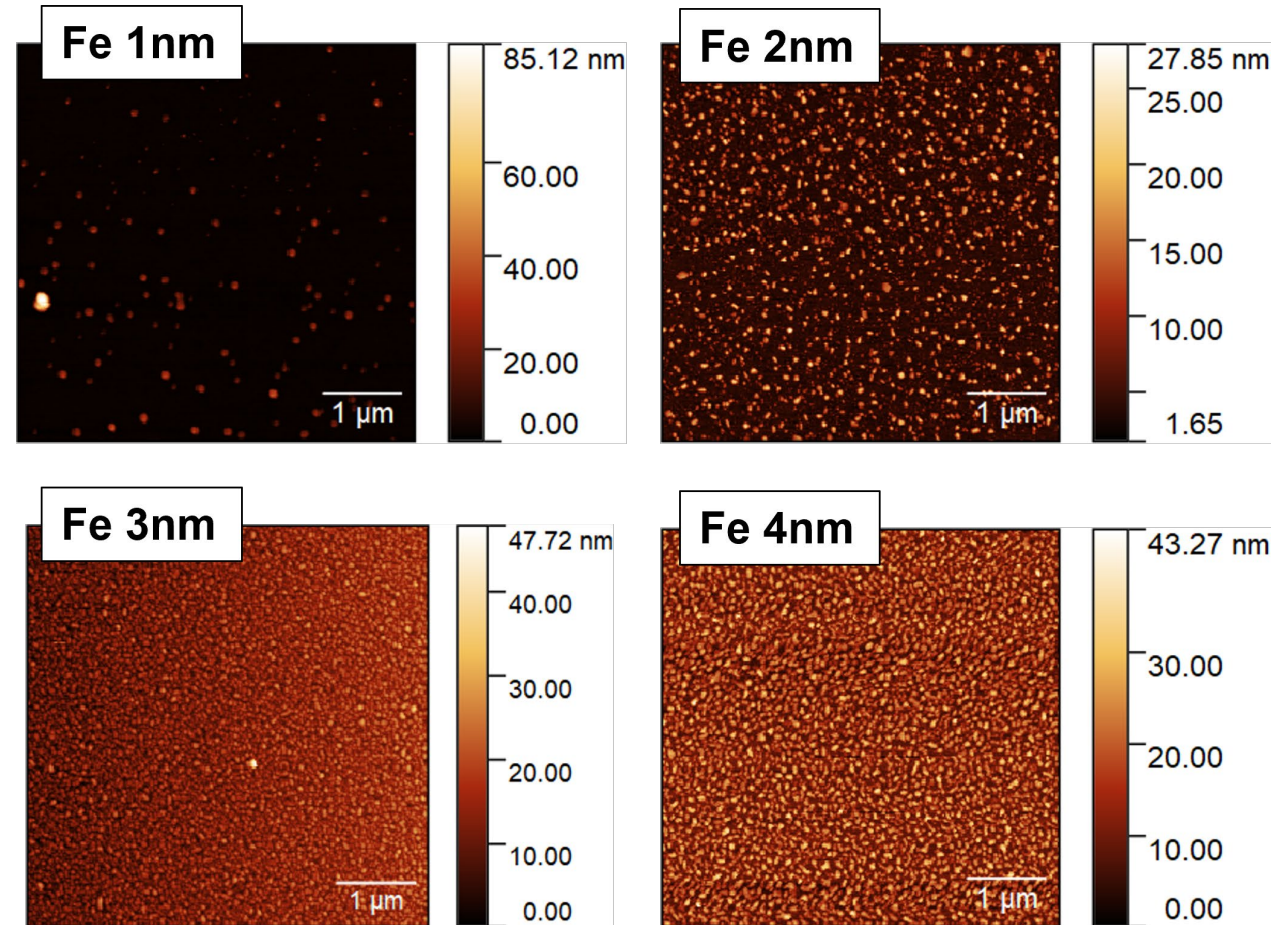
Acetone + IPA + MilliQ



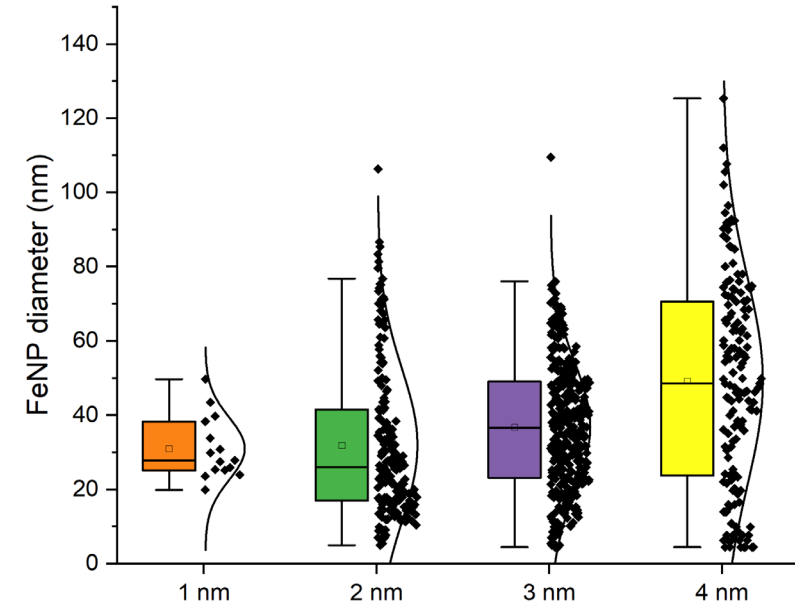
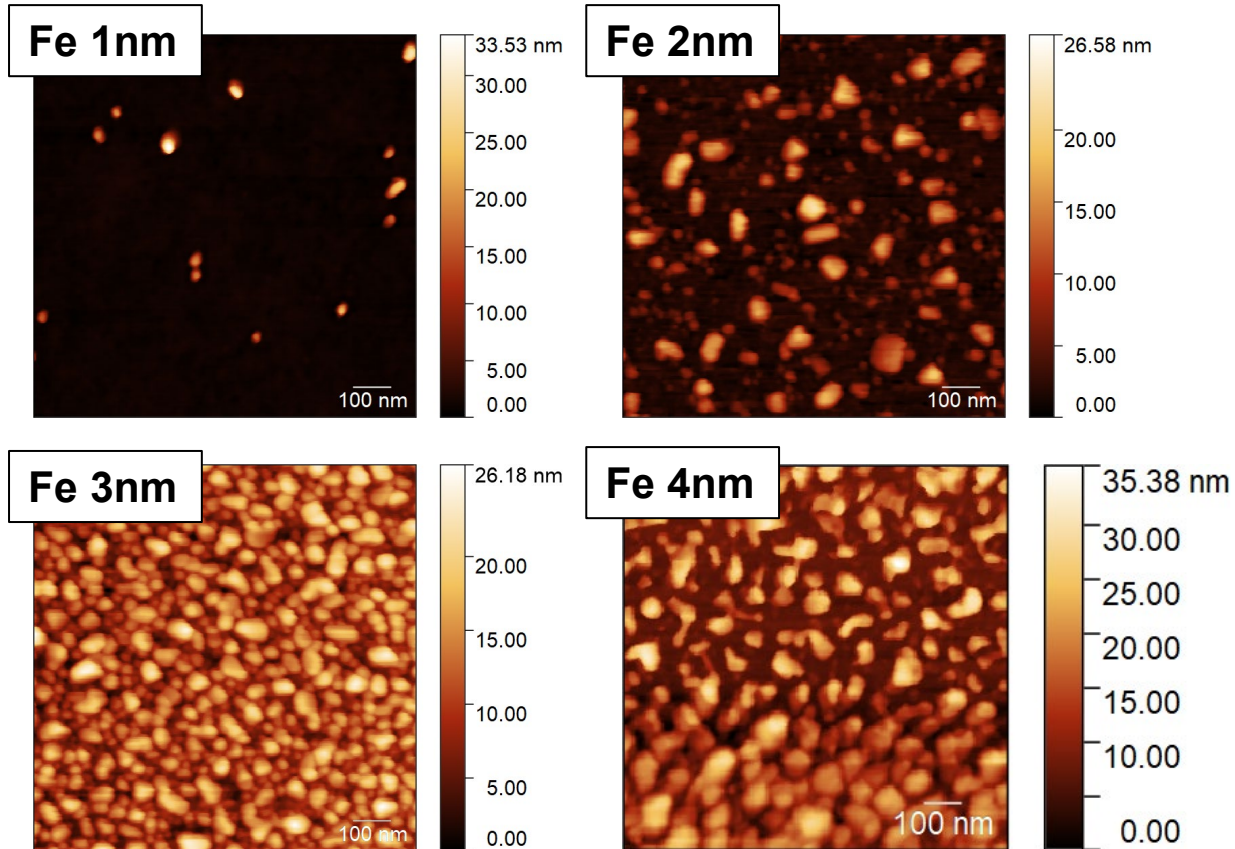
RCA1



- AFM characterization in Tapping mode
- Radius tip < 10 nm Si tip (PPP-NCHR)

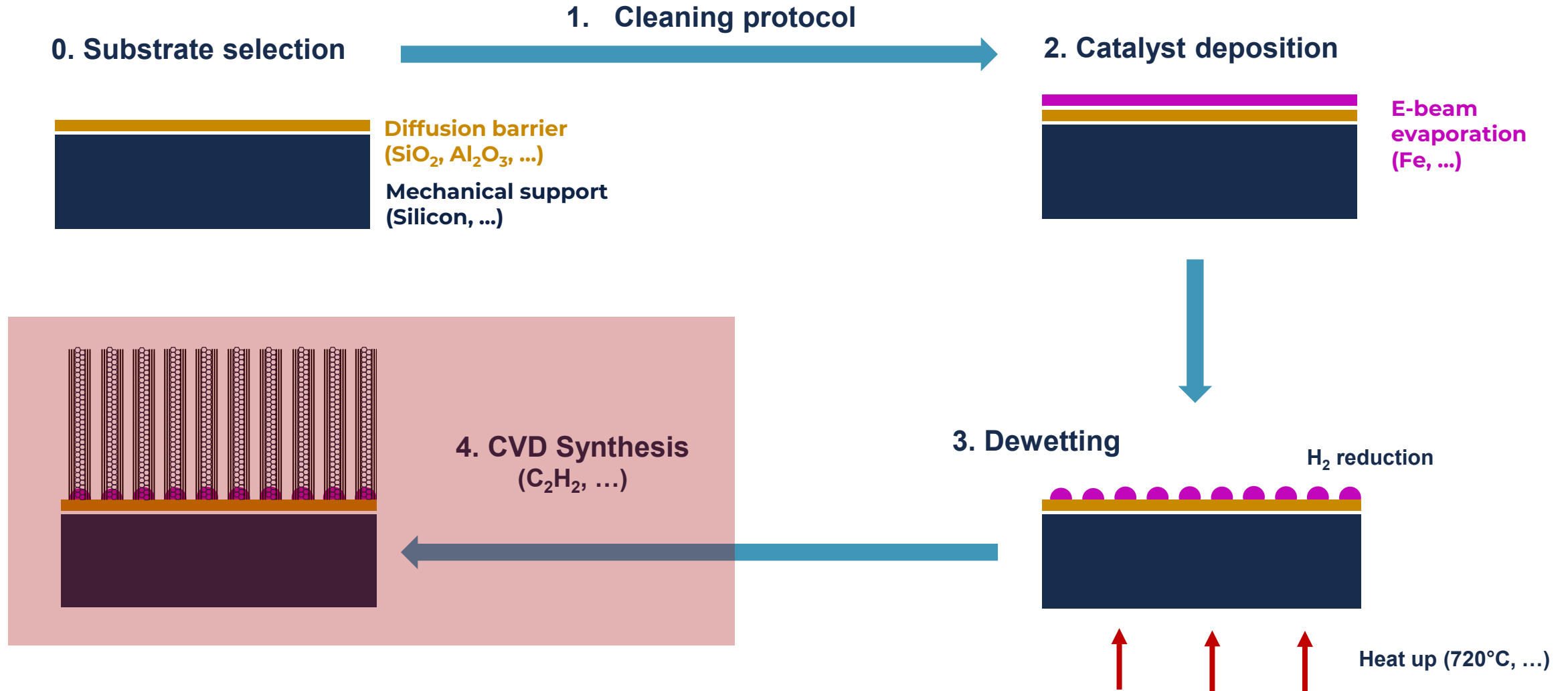


FeNPs Diameter analysis



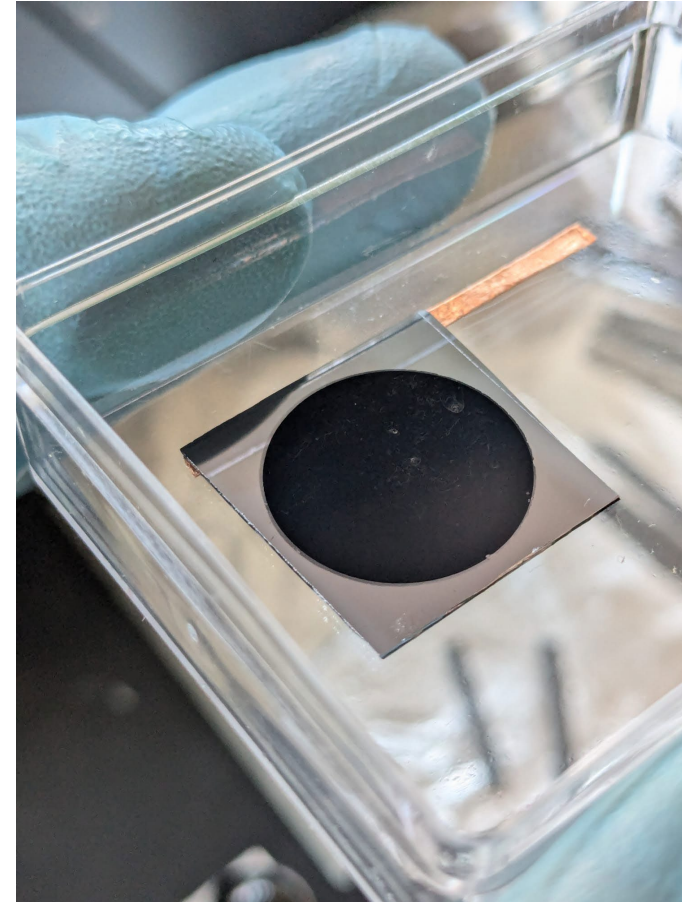
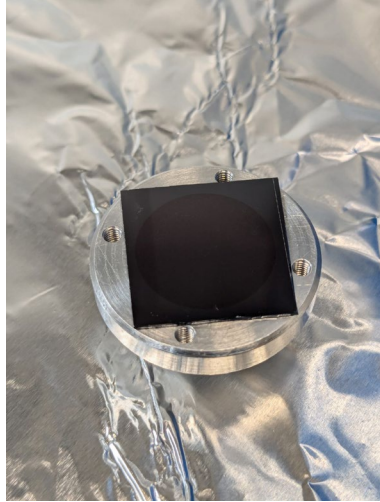
Fe Thickness (nm)	$\delta_{\text{FeNP}} \times 10^{10} \text{ cm}^{-2}$	Surface Coverage
1	0.21	1.2 %
2	1.98	21.9 %
3	3.38	44.1 %
4	1.54	38.7 %

Non-lithographic synthesis of VACNTs



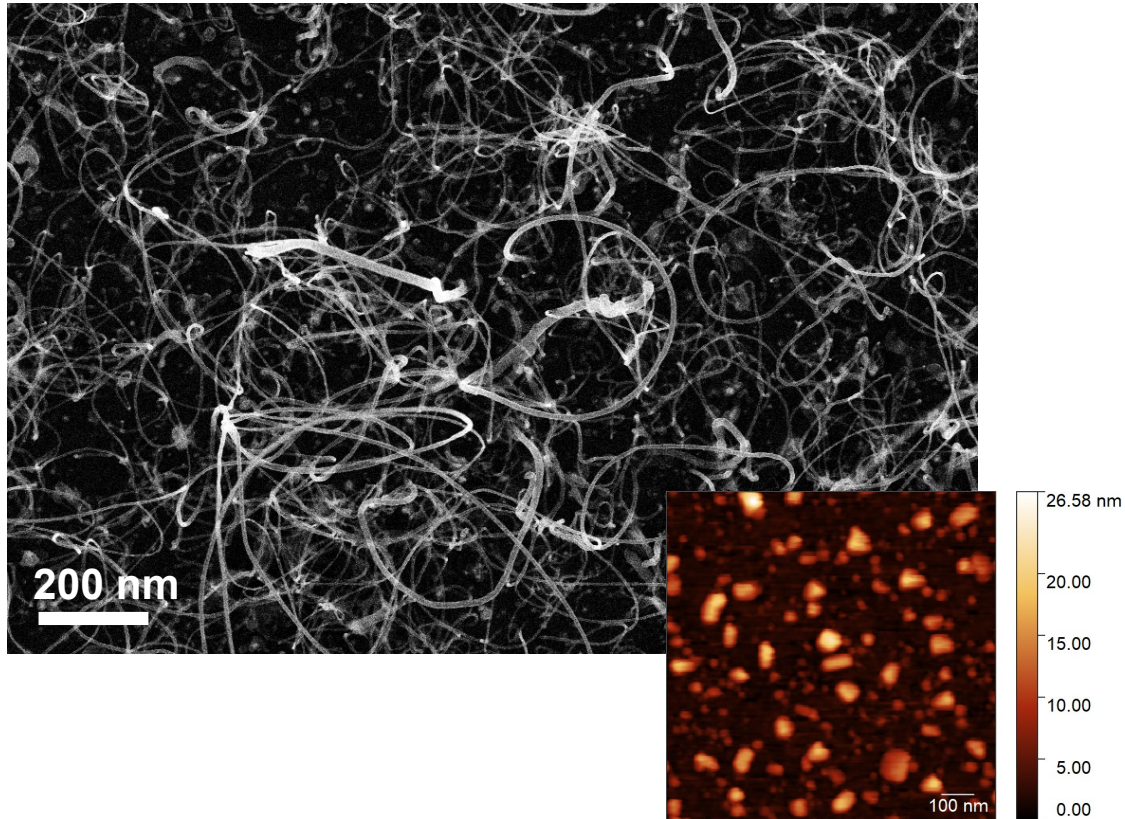
VACNTs synthesis

The very first VACNTs growth

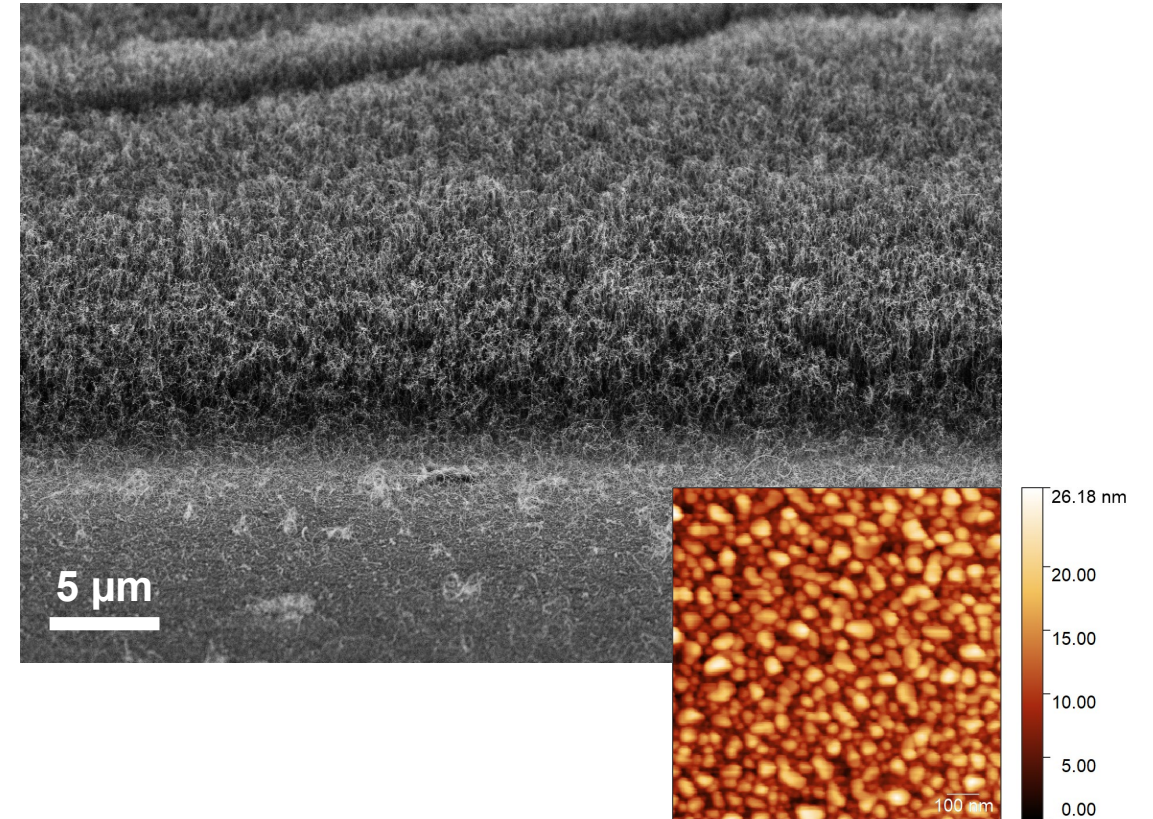


The very first problem

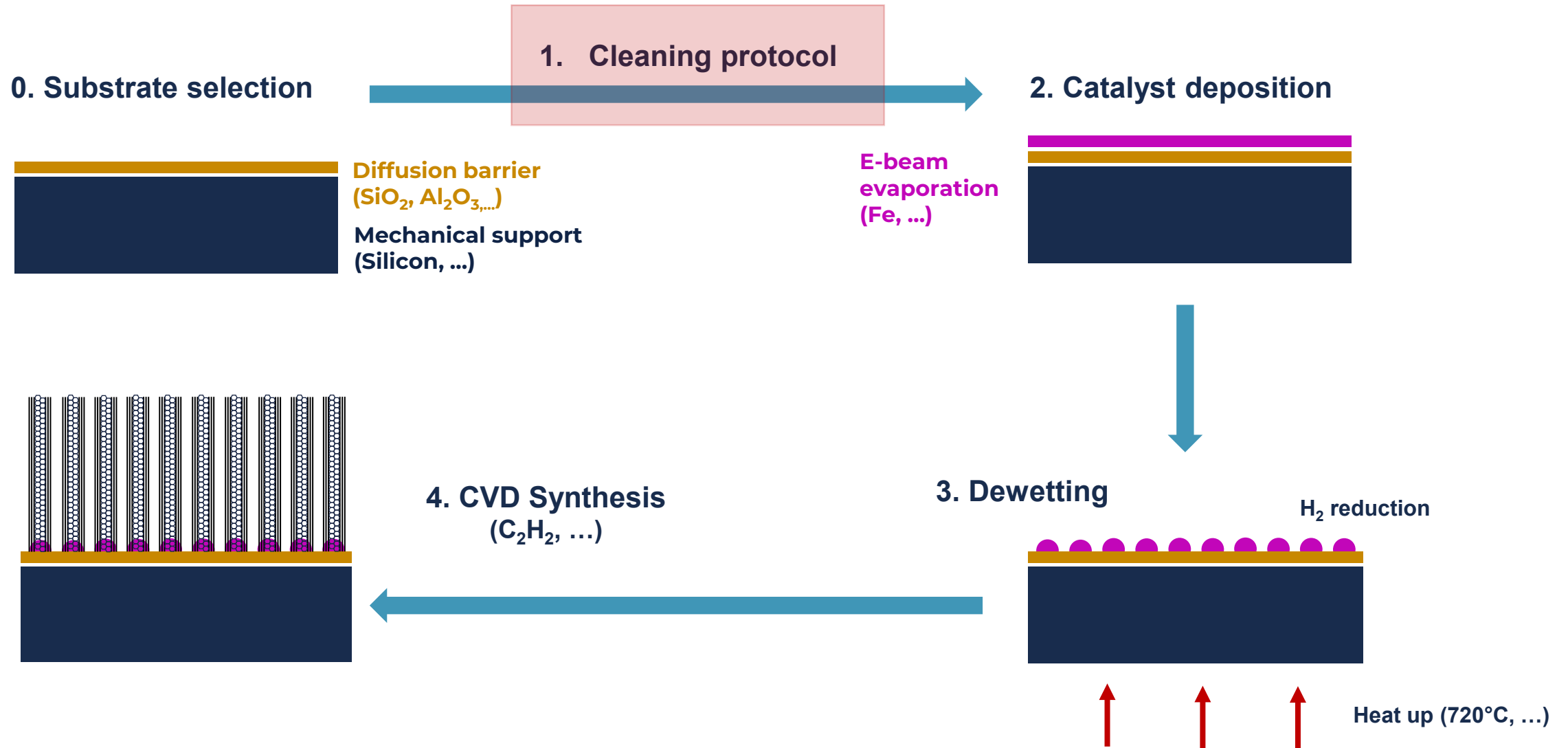
2 nm



3 nm

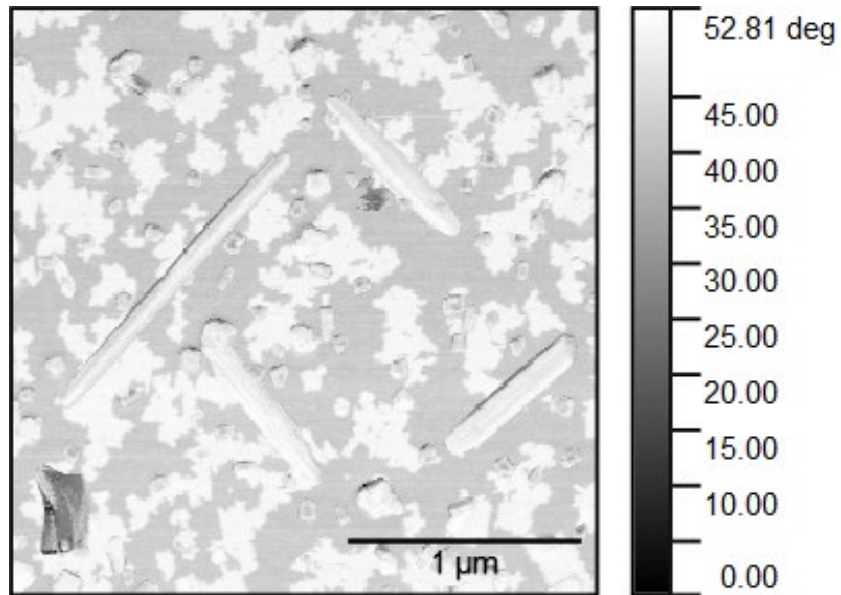


A step back...

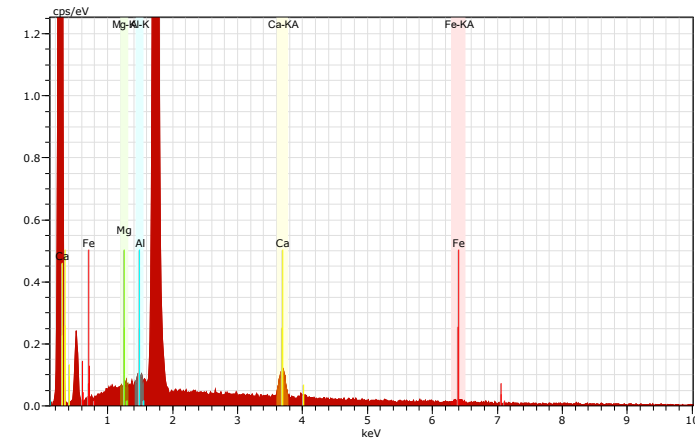
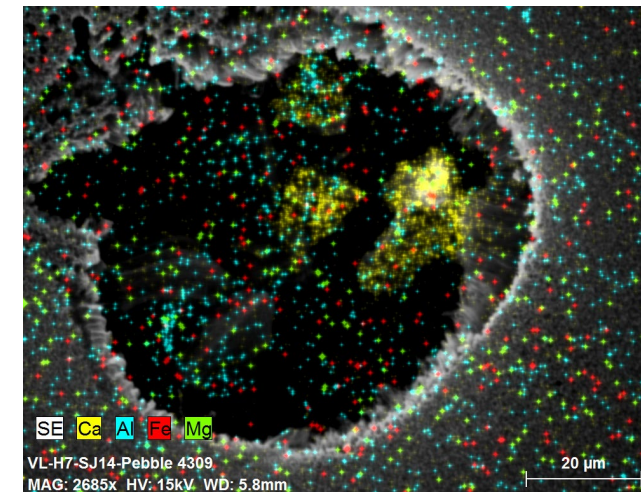


The importance of “fresh” Tipe I water

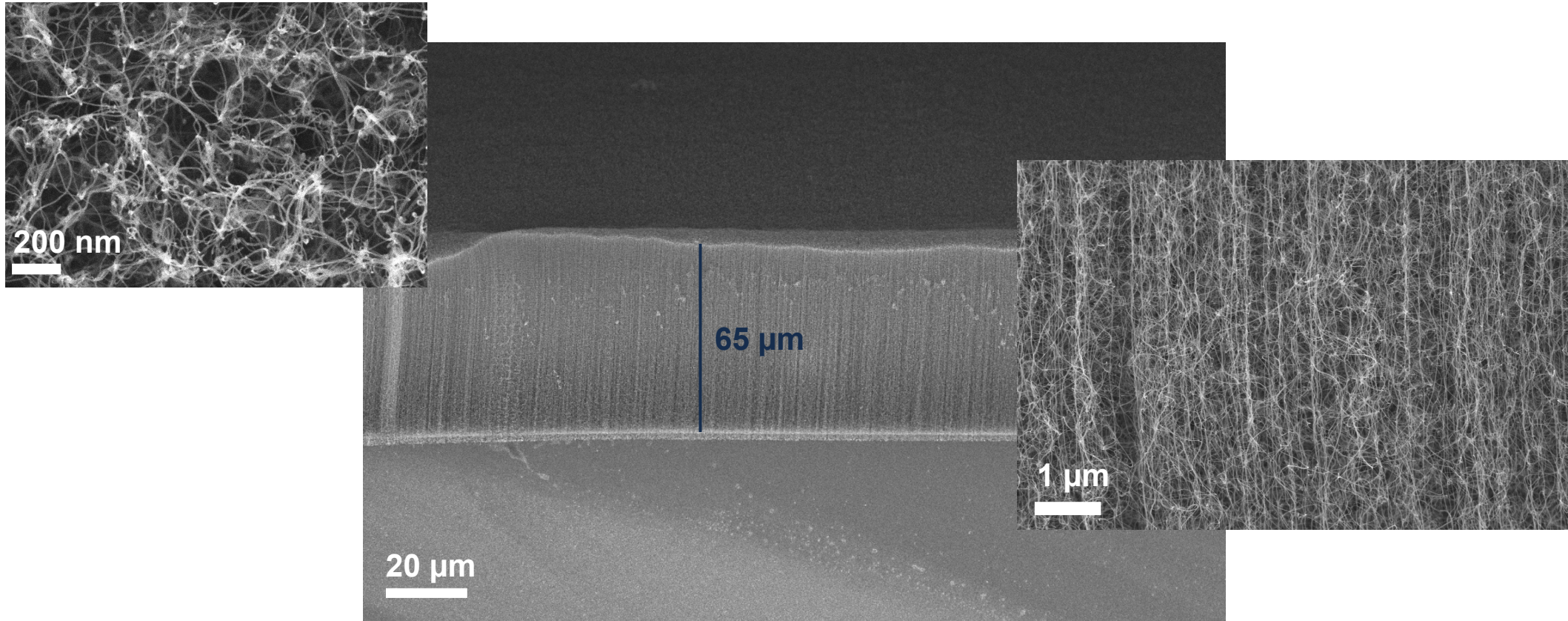
Phase diagram



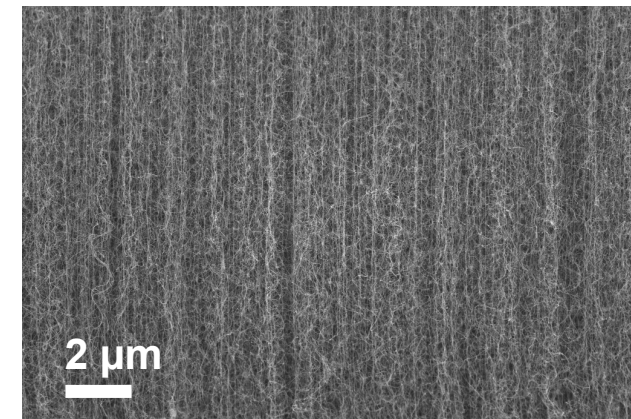
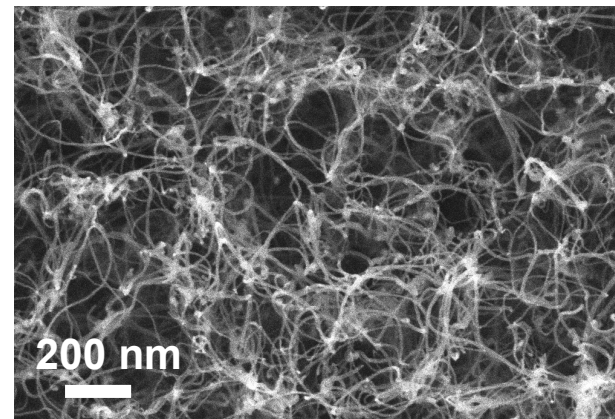
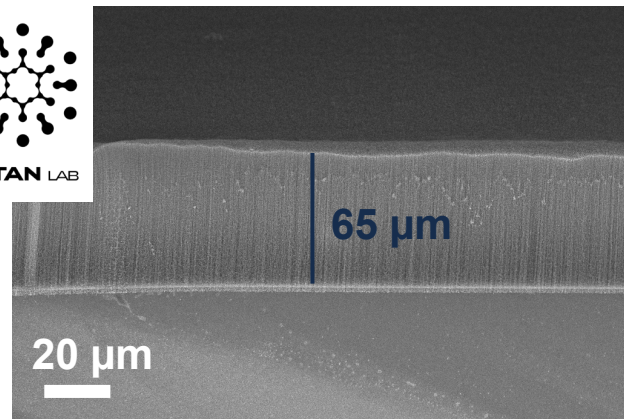
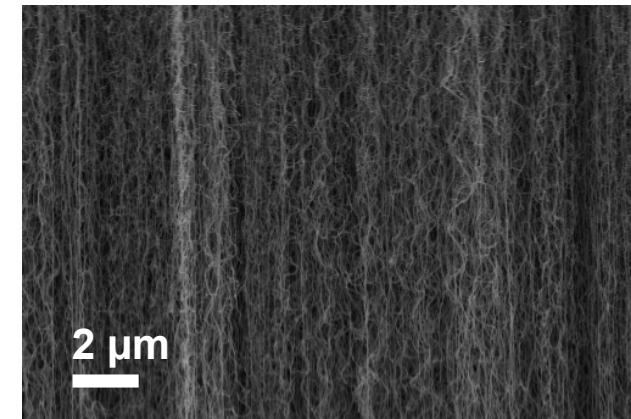
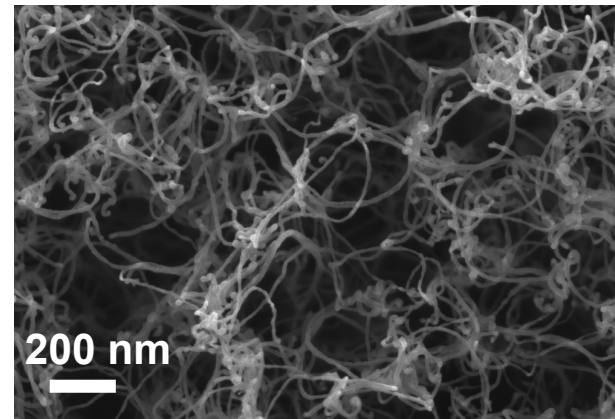
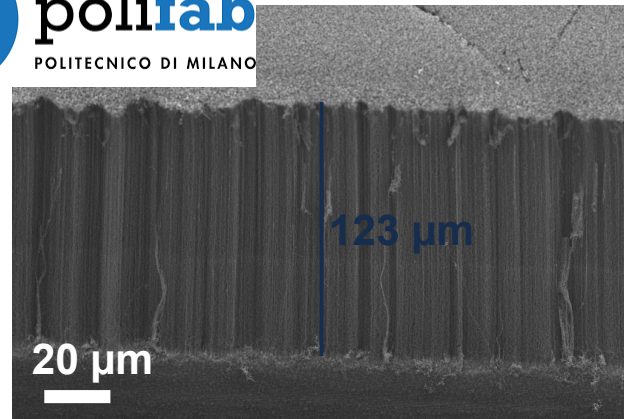
SEM-EDX



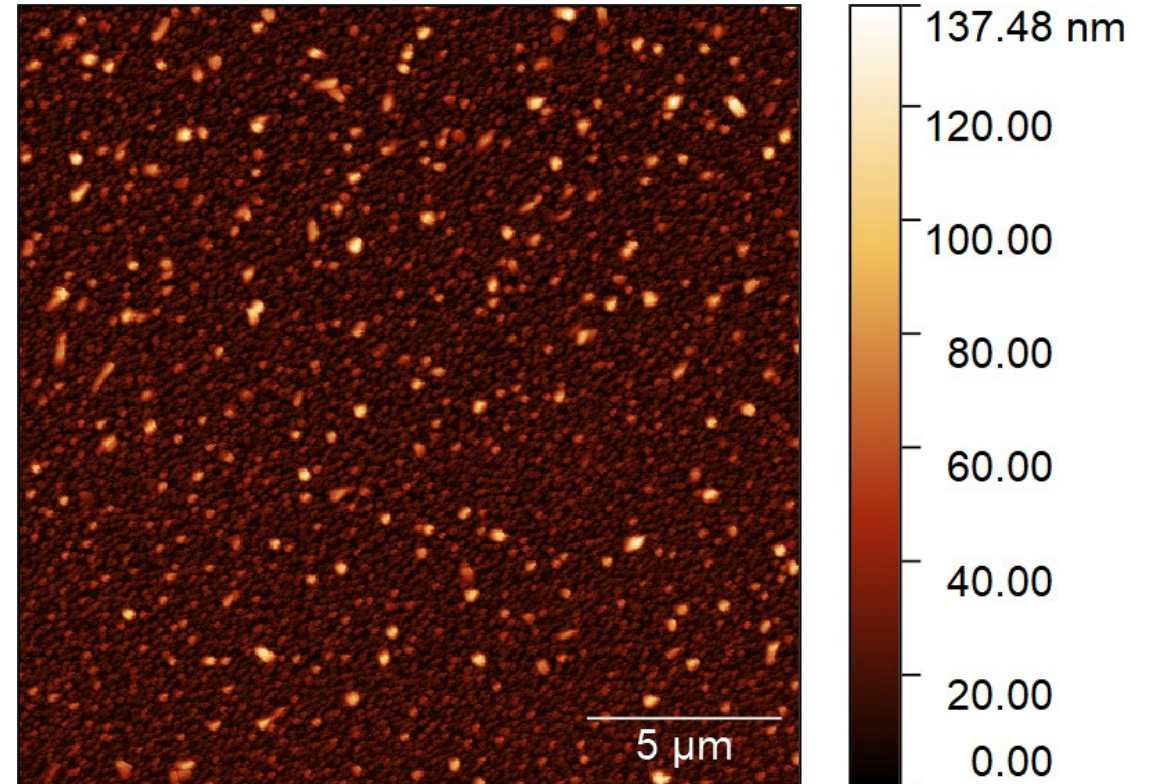
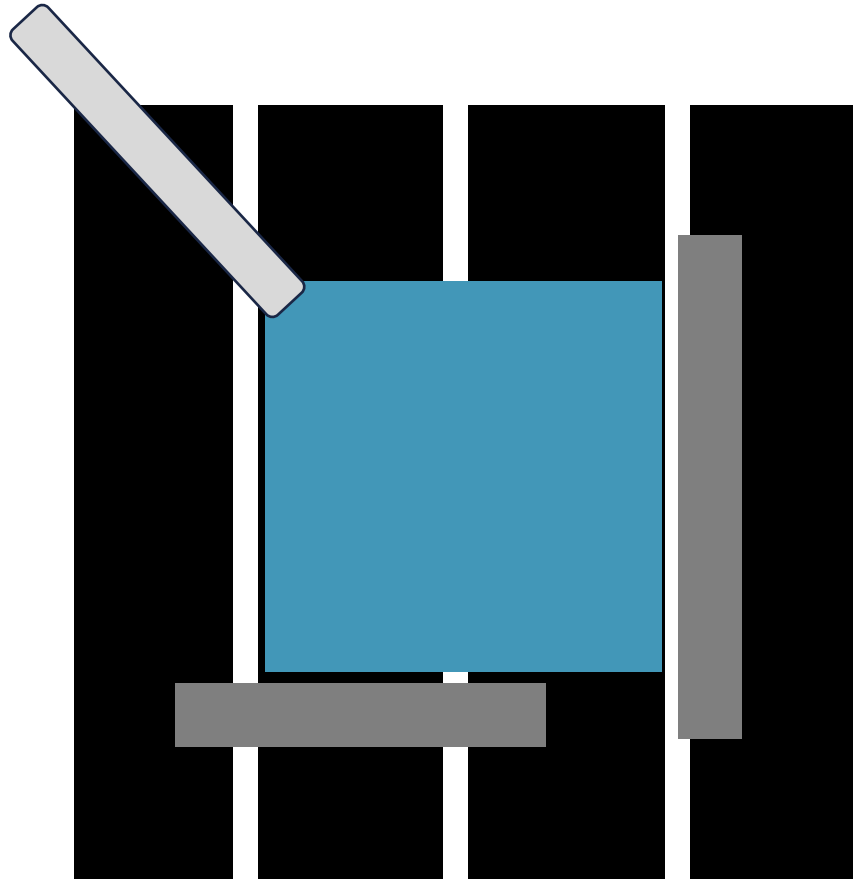
Protocol with “fresh MilliQ”



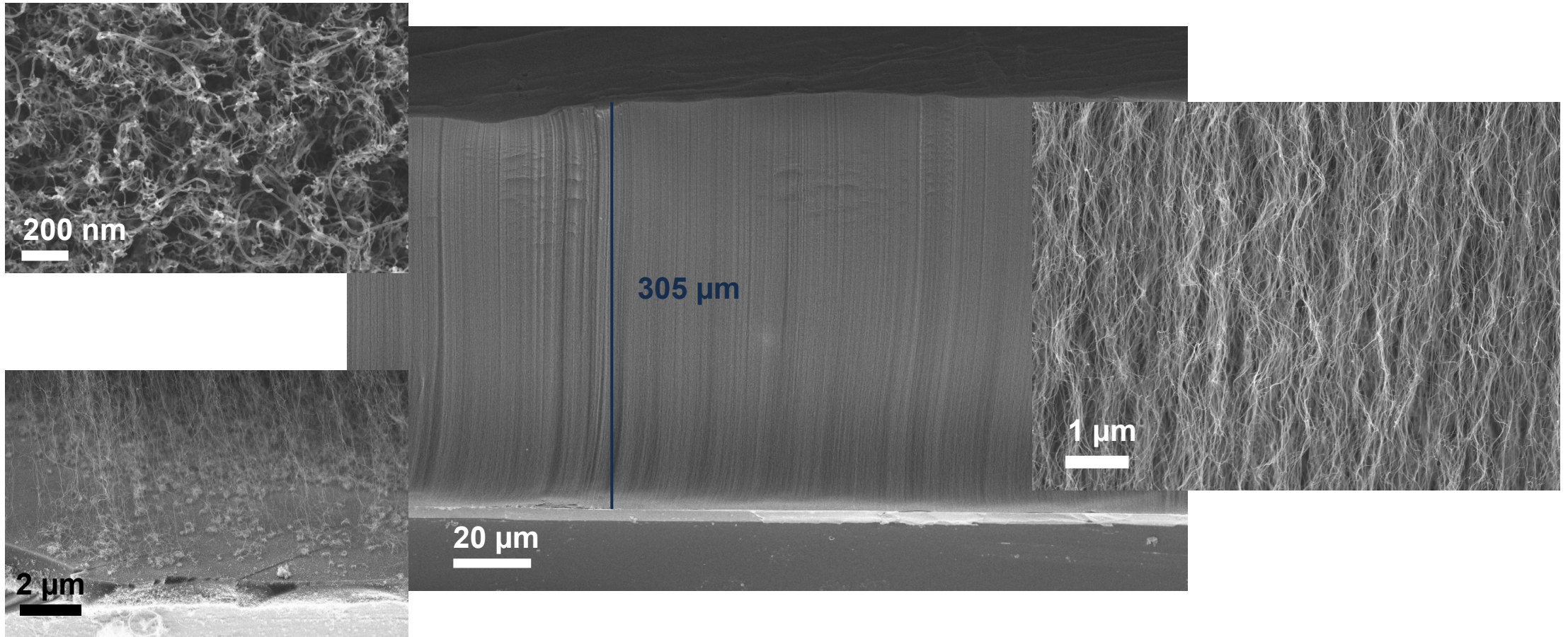
Comparison with Old samples



Uniform growth: remove holds

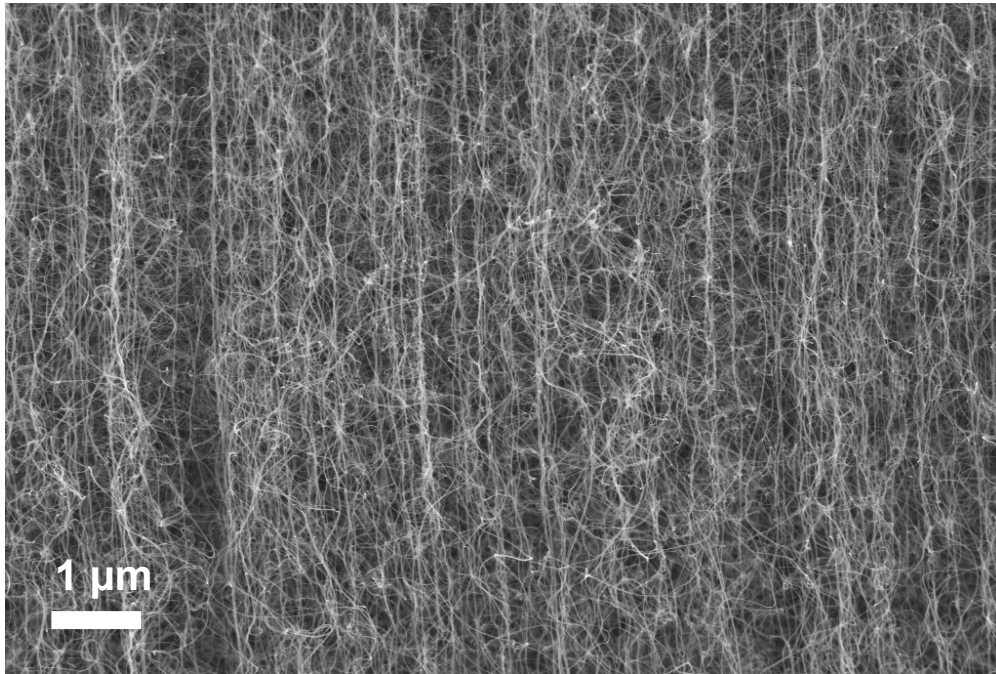


Uniform growth: remove holds

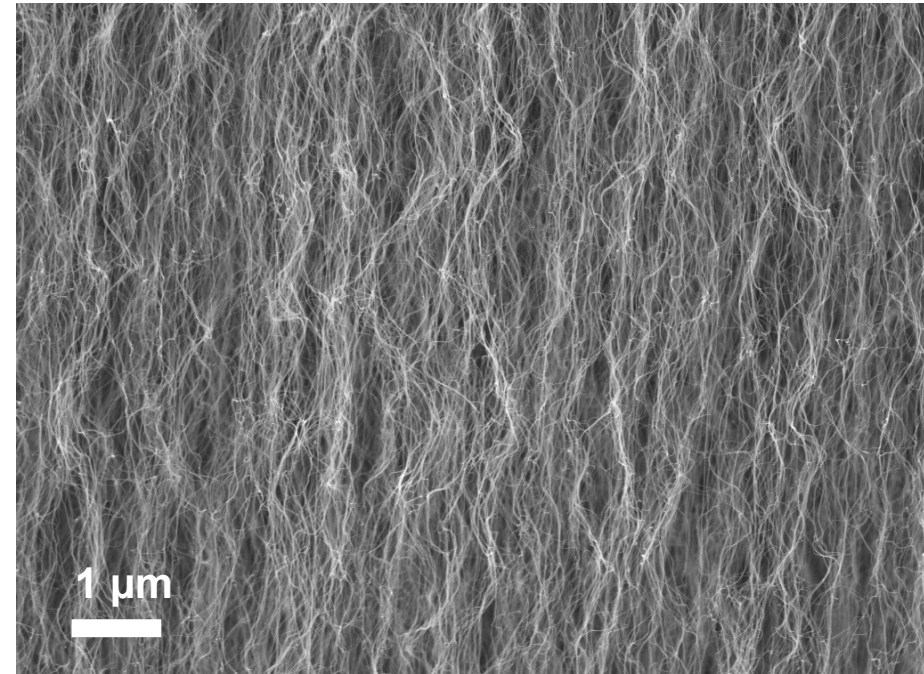


Comparison Fresh MilliQ and NoHolds

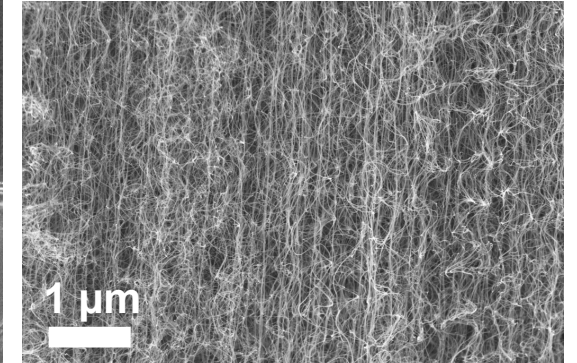
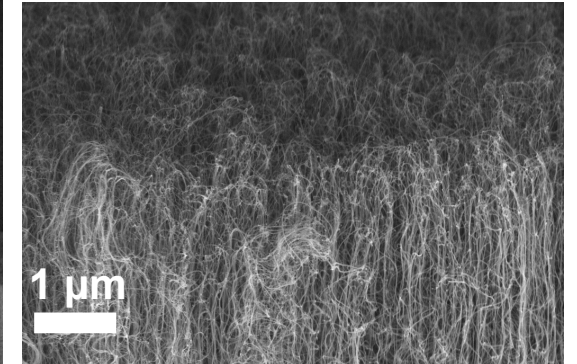
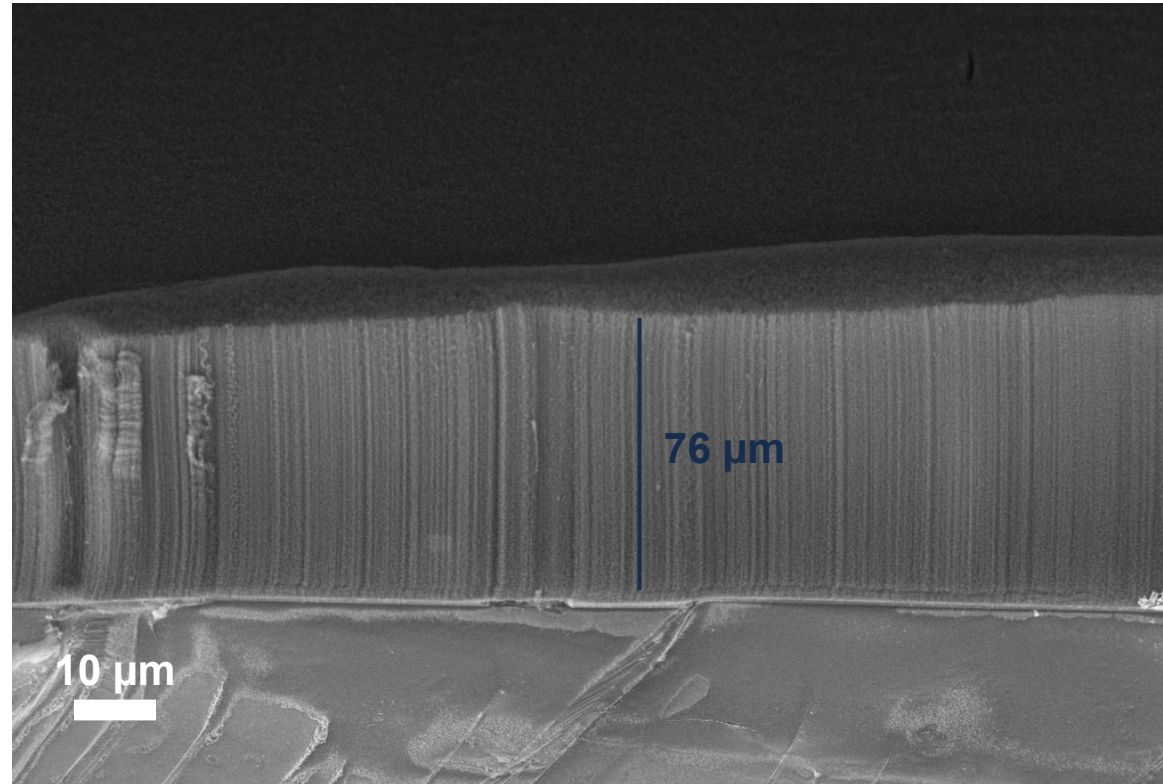
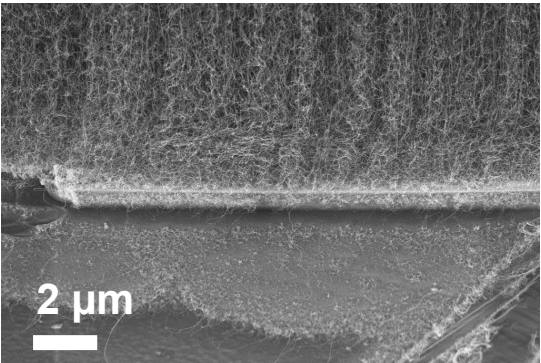
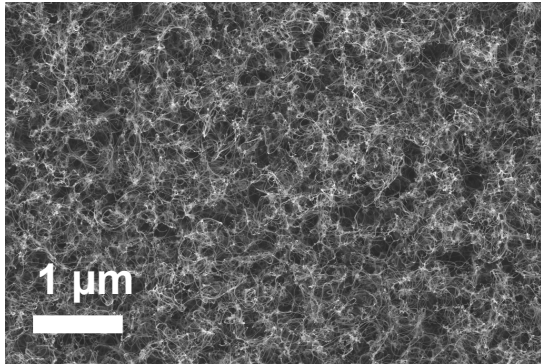
Holds

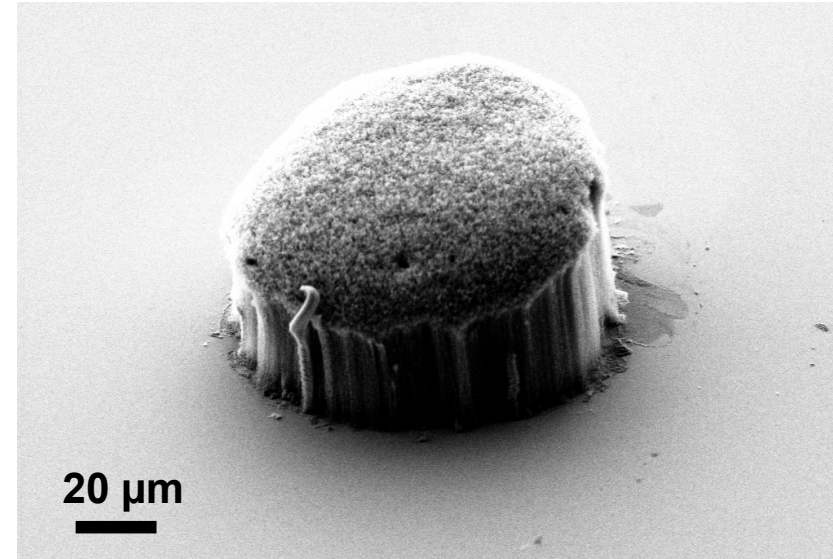
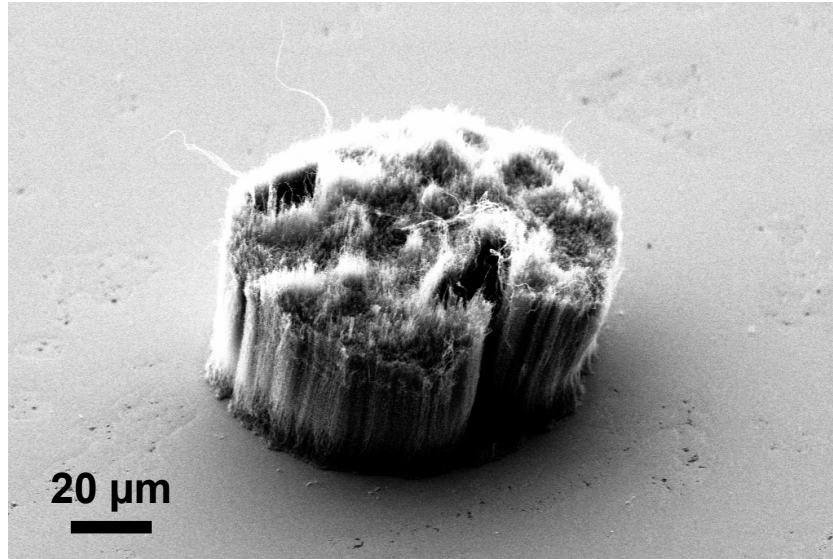


No holds



Flux hydrogen during synthesis

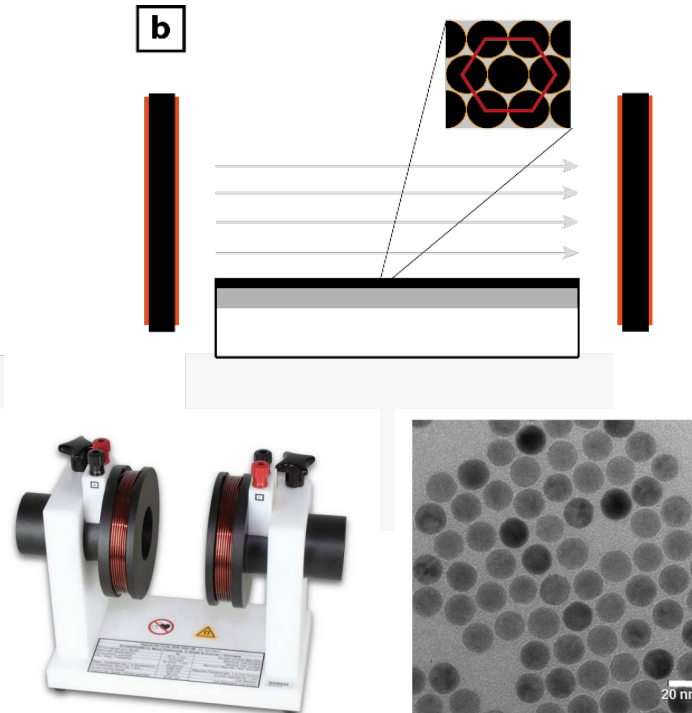
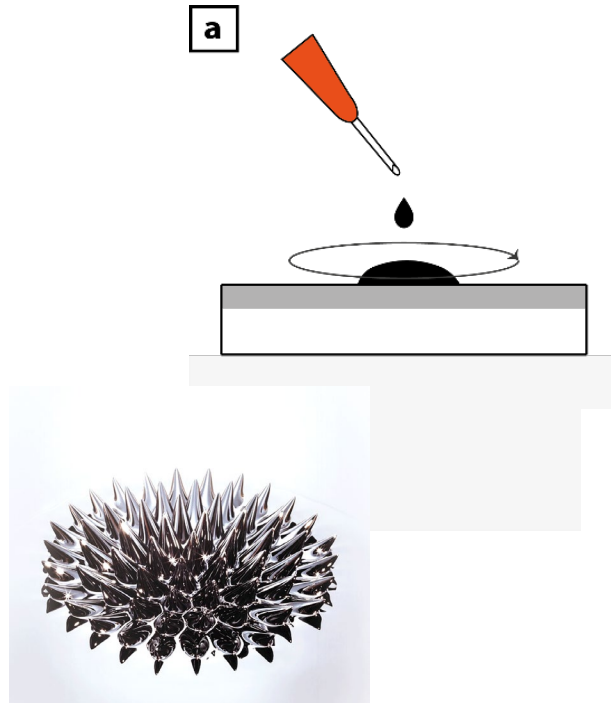




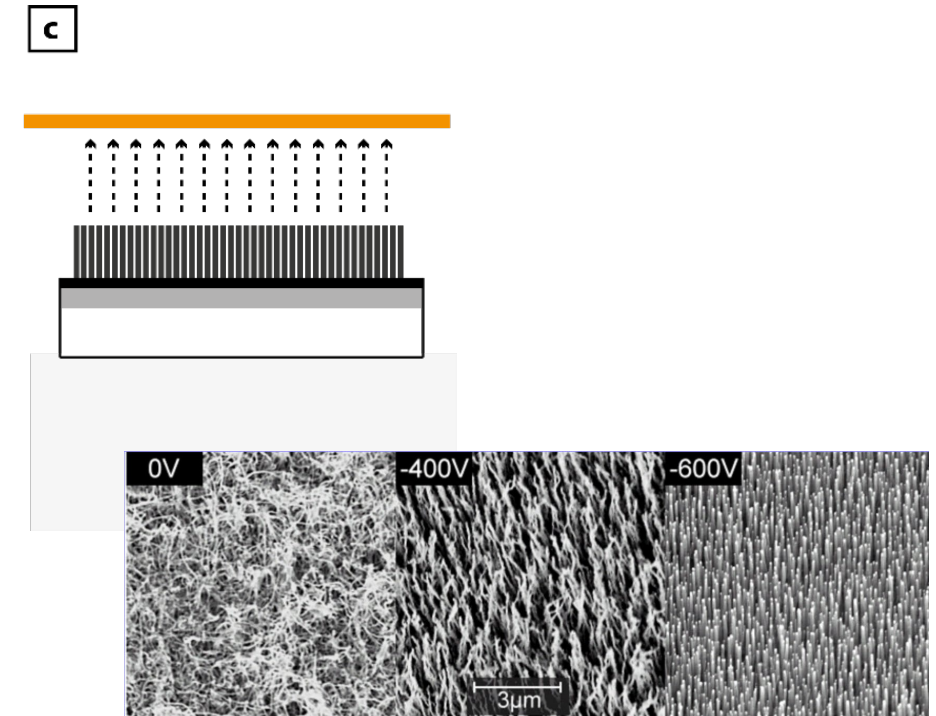
**Waiting for new SEM
micrographs of EBL
patterning (G. Pettinari)**

- Define reproducible protocol, **minimizing contamination** during cleaning, iron deposition and synthesis.
- Evaluate feasibility of **micropatterning**.
- Understand the role of **hydrogen plasma during annealing**.
- Evaluate the **crust removal with hydrogen plasma**.
- SEM of **microtome crust** cuts.
- Define a protocol for VACNTs **transfer printing on metal substrates** (copper, aluminium).
- Synthesis with **gas shower** and no more pipeline.

Future activities: Grant proposal



Theis-Bröhl, K. *et al.* Self-Assembled Layering of Magnetic Nanoparticles in a Ferrofluid on Silicon Surfaces. *ACS Appl. Mater. Interfaces* **10**, 5050–5060 (2018).



Chhowalla, M. *et al.* Growth process conditions of vertically aligned carbon nanotubes using plasma enhanced chemical vapor deposition. *Journal of Applied Physics* **90**, 5308–5317 (2001).

Thank you for the attention.
Any question?

Luca Cecchini

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